# EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|---|---|---|---|---|---|---|
| L1 | 37 | (sun near2 hee near2 kim).in. | US-PGPUB; USPAT; EPO; JPO; DERWENT | OR | OFF | 2007/11/29 12:23 |
| L2 | 9 | (sun near2 hee near2 kim).in. and silicon | US-PGPUB; USPAT; EPO; JPO; DERWENT | OR | OFF | 2007/11/29 12:24 |
| L3 | 3 | (sun near2 hee near2 kim).in. and silicon and silane | US-PGPUB; USPAT; EPO; JPO; DERWENT | OR | OFF | 2007/11/29 12:26 |
| L4 | 5 | (soo near2 suk near2 lee).in. and silicon and silane | US-PGPUB; USPAT; EPO; JPO; DERWENT | OR | OFF | 2007/11/29 12:27 |
| L5 | 52 | (geun near2 bae near2 lim).in. | US-PGPUB; USPAT; EPO; JPO; DERWENT | OR | OFF | 2007/11/29 12:27 |
| L6 | 17 | (geun near2 bae near2 lim).in. and silicon | US-PGPUB; USPAT; EPO; JPO; DERWENT | OR | OFF | 2007/11/29 12:27 |
| L7 | 2 | (geun near2 bae near2 lim).in. and silicon and silane | US-PGPUB; USPAT; EPO; JPO; DERWENT | OR | OFF | 2007/11/29 12:28 |
| L8 | 6 | (young near2 sun near2 lee).in. and silicon and silane | US-PGPUB; USPAT; EPO; JPO; DERWENT | OR | OFF | 2007/11/29 12:30 |
| L9 | 204 | silicon same silane same fluoro$8 same (pecvd or cvd or vapor) | US-PGPUB; USPAT; EPO; JPO; DERWENT | OR | OFF | 2007/11/29 12:31 |
| L10 | 0 | silicon same silane same fluoro$8 same (pecvd or cvd or vapor) and fluoroakylsilane | US-PGPUB; USPAT; EPO; JPO; DERWENT | OR | OFF | 2007/11/29 12:32 |
| L11 | 5 | silicon same silane same fluoro$8 same (pecvd or cvd or vapor) and fluoroalkylsilane | US-PGPUB; USPAT; EPO; JPO; DERWENT | OR | OFF | 2007/11/29 12:32 |

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$%^STN;HighlightOn=  ***;HighlightOff=***  ;

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 NEWS  3  JUL 02   SCISEARCH enhanced with complete author names
 NEWS  4  JUL 02   CHEMCATS accession numbers revised
 NEWS  5  JUL 02   CA/CAplus enhanced with utility model patents from China
 NEWS  6  JUL 16   CAplus enhanced with French and German abstracts
 NEWS  7  JUL 18   CA/CAplus patent coverage enhanced
 NEWS  8  JUL 26   USPATFULL/USPAT2 enhanced with IPC reclassification
 NEWS  9  JUL 30   USGENE now available on STN
 NEWS 10  AUG 06   CAS REGISTRY enhanced with new experimental property tags
 NEWS 11  AUG 06   FSTA enhanced with new thesaurus edition
 NEWS 12  AUG 13   CA/CAplus enhanced with additional kind codes for granted
                   patents
 NEWS 13  AUG 20   CA/CAplus enhanced with CAS indexing in pre-1907 records
 NEWS 14  AUG 27   Full-text patent databases enhanced with predefined
                   patent family display formats from INPADOCDB
 NEWS 15  AUG 27   USPATOLD now available on STN
 NEWS 16  AUG 28   CAS REGISTRY enhanced with additional experimental
                   spectral property data
 NEWS 17  SEP 07   STN AnaVist, Version 2.0, now available with Derwent
                   World Patents Index
 NEWS 18  SEP 13   FORIS renamed to SOFIS
 NEWS 19  SEP 13   INPADOCDB enhanced with monthly SDI frequency
 NEWS 20  SEP 17   CA/CAplus enhanced with printed CA page images from
                   1967-1998
 NEWS 21  SEP 17   CAplus coverage extended to include traditional medicine
                   patents
 NEWS 22  SEP 24   EMBASE, EMBAL, and LEMBASE reloaded with enhancements
 NEWS 23  OCT 02   CA/CAplus enhanced with pre-1907 records from Chemisches
                   Zentralblatt
 NEWS 24  OCT 19   BEILSTEIN updated with new compounds
 NEWS 25  NOV 15   Derwent Indian patent publication number format enhanced
 NEWS 26  NOV 19   WPIX enhanced with XML display format

 NEWS EXPRESS  19 SEPTEMBER 2007:  CURRENT WINDOWS VERSION IS V8.2,
               CURRENT MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP),
               AND CURRENT DISCOVER FILE IS DATED 19 SEPTEMBER 2007.

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FILE 'HOME' ENTERED AT 11:57:58 ON 29 NOV 2007

=> file reg
COST IN U.S. DOLLARS                                  SINCE FILE      TOTAL
                                                         ENTRY     SESSION
FULL ESTIMATED COST                                       0.21        0.21
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FILE 'REGISTRY' ENTERED AT 11:58:07 ON 29 NOV 2007
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DICTIONARY FILE UPDATES: 28 NOV 2007 HIGHEST RN 956214-95-2

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L1 STRUCTURE UPLOADED

=> s l1 full
FULL SEARCH INITIATED 11:58:23 FILE 'REGISTRY'
FULL SCREEN SEARCH COMPLETED - 501593 TO ITERATE

100.0% PROCESSED 501593 ITERATIONS 40926 ANSWERS
SEARCH TIME: 00.00.03

L2 40926 SEA SSS FUL L1

=>
Uploading C:\Program Files\Stnexp\Queries\10765366\str2.str

L3 STRUCTURE UPLOADED

=> s l3 full
FULL SEARCH INITIATED 11:58:45 FILE 'REGISTRY'
FULL SCREEN SEARCH COMPLETED - 22367 TO ITERATE

100.0% PROCESSED 22367 ITERATIONS 669 ANSWERS
SEARCH TIME: 00.00.13

L4 669 SEA SSS FUL L3

=> file caplus

| COST IN U.S. DOLLARS | SINCE FILE ENTRY | TOTAL SESSION |
|---|---|---|
| FULL ESTIMATED COST | 344.20 | 344.41 |

FILE 'CAPLUS' ENTERED AT 11:59:27 ON 29 NOV 2007
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FILE COVERS 1907 - 29 Nov 2007 VOL 147 ISS 23
FILE LAST UPDATED: 28 Nov 2007 (20071128/ED)

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=> s l4 and l2
          1792 L4
         61465 L2
L5        1792 L4 AND L2

=> s l5 and silicon
        854311 SILICON
           416 SILICONS
        854454 SILICON
                 (SILICON OR SILICONS)
L6         316 L5 AND SILICON

=> dup remove l6
PROCESSING COMPLETED FOR L6
L7          316 DUP REMOVE L6 (0 DUPLICATES REMOVED)

=> s l7 and (vapor)
L8          316 S L7
        549461 VAPOR
         73279 VAPORS
        592558 VAPOR
                 (VAPOR OR VAPORS)
L9           51 L8 AND (VAPOR)

=> dup remove l9
PROCESSING COMPLETED FOR L9
L10          51 DUP REMOVE L9 (0 DUPLICATES REMOVED)

=> d ibib abs hitstr 1-5

L10  ANSWER 1 OF 51  CAPLUS  COPYRIGHT 2007 ACS on STN
ACCESSION NUMBER:          2007:1000213  CAPLUS <<LOGINID::20071129>>
DOCUMENT NUMBER:           147:355832
TITLE:                     Digital magnetofluidic devices and methods
INVENTOR(S):               Hernandez, Sonia Melle; Gomez, Ana N.; Picraux, S.
                           Thomas; Gust, John Devens; Hayes, Mark; Lindsay,
                           Solitaire; Garcia, Antonio A.; Wang, Joseph;
                           Vazquez-Alvarez, Terannie
PATENT ASSIGNEE(S):        Arizona Board of Regents for and on Behalf of Arizona
                           State University, USA
SOURCE:                    PCT Int. Appl., 118pp.
                           CODEN: PIXXD2
DOCUMENT TYPE:             Patent
LANGUAGE:                  English
FAMILY ACC. NUM. COUNT:    1
PATENT INFORMATION:

      PATENT NO.           KIND   DATE        APPLICATION NO.          DATE
      ---------------      ----   --------    --------------------     --------
      WO 2007101174         A2    20070907    WO 2007-US62842          20070227
          W:  AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH,
              CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD,
              GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN,
              KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LV, LY, MA, MD, MG, MK,
              MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO,
              RS, RU, SC, SD, SE, SG, SK, SL, SM, SV, SY, TJ, TM, TN, TR, TT,
              TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW
          RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE,
              IS, IT, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ,
              CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH,
              GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY,
              KG, KZ, MD, RU, TJ, TM
PRIORITY APPLN. INFO.:                    US 2006-777679P      P  20060227
AB    Disclosed are devices and methods for moving and controlling droplets of
      fluids on hydrophobic surfaces through the use of magnetic fields.  For
      example, droplets can be moved, immobilized, dispensed, coalesced, and/or
      divided.  Also disclosed is a digital magnetofluidic device comprising a
      hydrophobic surface; a magnetically active fluid droplet in contact with
      the surface; and a magnetic field coupled with at least a portion of the
      droplet.  Also disclosed is a digital isoelec. focusing method using the
      devices and methods.  Also disclosed are digital microelectrochem.
      detection methods and digital microelectrochem. reaction methods.  This
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abstr. is intended as a scanning tool for purposes of searching in the particular art and is not intended to be limiting of the present invention.

IT ***51851-37-7*** , 1H,1H,2H,2H-Perfluorooctyltriethoxysilane
RL: RCT (Reactant); RACT (Reactant or reagent)
(digital magnetofluidic devices and methods for controlling droplet movement)

RN 51851-37-7 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA INDEX NAME)

/ Structure 1 in file .gra /

IT ***531506-10-2*** ***691013-81-7*** , 2-[3-(Triethoxysilyl)propylaminocarbonylamino]-6-methyl-4(1H)-pyrimidinone
RL: TEM (Technical or engineered material use); USES (Uses)
(digital magnetofluidic devices and methods for controlling droplet movement)

RN 531506-10-2 CAPLUS
CN 2-Propenoic acid, 2-methyl-, 3-(triethoxysilyl)propyl ester, polymer with .alpha.-(2-methyl-1-oxo-2-propen-1-yl)-.omega.-methoxypoly(oxy-1,2-ethanediyl), graft (CA INDEX NAME)

CM 1

CRN 26915-72-0
CMF (C2 H4 O)n C5 H8 O2
CCI PMS

/ Structure 2 in file .gra /

CM 2

CRN 21142-29-0
CMF C13 H26 O5 Si

/ Structure 3 in file .gra /

RN 691013-81-7 CAPLUS
CN Urea, N-(1,6-dihydro-4-methyl-6-oxo-2-pyrimidinyl)-N'-[3-(triethoxysilyl)propyl]- (CA INDEX NAME)

/ Structure 4 in file .gra /

L10 ANSWER 2 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
ACCESSION NUMBER: 2007:933138 CAPLUS <<LOGINID::20071129>>
DOCUMENT NUMBER: 147:290978
TITLE: Method of processing a biological and/or chemical sample
INVENTOR(S): Pipper, Juergen; Hsieh, Tseng-Ming; Neuzil, Pavel
PATENT ASSIGNEE(S): Agency for Science, Technology and Research, Singapore
SOURCE: PCT Int. Appl., 67pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|---|---|---|---|---|
| WO 2007094739 | A1 | 20070823 | WO 2006-SG29 | 20060213 |

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, LY, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH,

GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM

PRIORITY APPLN. INFO.: WO 2006-SG29 20060213

AB The invention provides a method of processing a biol. and/or chem. sample. The method includes providing a fluid droplet, which includes an inner phase and an outer phase. The outer phase is immiscible with the inner phase, and the outer phase is surrounding the inner phase. The inner phase includes the biol. and/or chem. sample. The fluid droplet also comprises magnetically attractable matter. The method also includes providing at least one surface, which is of such a texture and such a wettability for the fluid of the inner phase of the fluid droplet, that the fluid droplet remains intact upon being contacted therewith. The method further includes disposing the fluid droplet onto the at least one surface. The method also includes performing a process on the biol. and/or chem. sample in the fluid droplet.

IT ***101947-16-4***
RL: MOA (Modifier or additive use); USES (Uses)
(method of processing biol. and/or chem. sample in fluid droplet)

RN 101947-16-4 CAPLUS

CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 5 in file .gra /

REFERENCE COUNT: 5 THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L10 ANSWER 3 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2007:970042 CAPLUS <<LOGINID::20071129>>

DOCUMENT NUMBER: 147:288568

TITLE: Thin organic alignment layers with a batch process for liquid crystal displays

INVENTOR(S): Ong, Hiap L.

PATENT ASSIGNEE(S): Kyoritsu Optronics Co., Ltd., Taiwan

SOURCE: U.S. Pat. Appl. Publ., 16pp., Cont.-in-part of U.S. Ser. No. 227,570.
CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|---|---|---|---|---|
| US 2007202253 | A1 | 20070830 | US 2006-607246 | 20061201 |
| US 2007059438 | A1 | 20070315 | US 2005-227570 | 20050915 |
| PRIORITY APPLN. INFO.: | | | US 2005-227570 A2 | 20050915 |

AB A method to form alignment layers on a substrate of an LCD is disclosed. The substrate is placed in a vacuum chamber and undergoes a purging process. The purging process heats the substrates and removes water ***vapor*** from the vacuum chamber. Specifically, the vacuum chamber is evacuated to a low pressure and refilled with a preheated inert gas. Evacuation of the vacuum chamber and refilling of the vacuum chamber is repeated several times. The alignment layer is then deposited using ***vapor*** deposition. Alternatively, plasma enhanced ***vapor*** deposition can be used for depositing the alignment layer. Furthermore, plasma cleaning prior to the deposition of the alignment layer can used clean the substrate.

IT ***2943-75-1*** , Octyltriethoxysilane ***51851-37-7*** , 1H,1H,2H,2H-Perfluorooctyltriethoxysilane
RL: TEM (Technical or engineered material use); USES (Uses)
(thin org. alignment layers with a batch process for liq. crystal displays)

RN 2943-75-1 CAPLUS

CN Silane, triethoxyoctyl- (CA INDEX NAME)

/ Structure 6 in file .gra /

RN 51851-37-7 CAPLUS

CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA INDEX NAME)

/ Structure 7 in file .gra /

L10 ANSWER 4 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
ACCESSION NUMBER: 2007:980718 CAPLUS <<LOGINID::20071129>>
DOCUMENT NUMBER: 147:376451
TITLE: Method for constructing surface enhanced substrate with metal ordered structure
INVENTOR(S): Lu, Nan; Yang, Bingjie; Huang, Chunyu; Chi, Lifeng
PATENT ASSIGNEE(S): Jilin University, Peop. Rep. China
SOURCE: Faming Zhuanli Shenqing Gongkai Shuomingshu, 30pp.
CODEN: CNXXEV
DOCUMENT TYPE: Patent
LANGUAGE: Chinese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|---|---|---|---|---|
| CN 101024483 | A | 20070829 | CN 2007-10055453 | 20070327 |
| PRIORITY APPLN. INFO.: | | | CN 2007-10055453 | 20070327 |

AB The invention relates to construct ordered structure on a substrate and metal ordered structure by using the ordered structure substrate as template, and the metal ordered structure can obviously enhance the probe mol. signal during the Raman detection process. The title method comprises: (1) selecting inorg. substrate or polymer substrate, cleaning, and treating to obtain conductive substrate, (2) constructing polymer barrier layer or different functional groups and ordered nano/micro structure by photolithog., electron beam etching, nano-imprinting, ***vapor*** deposition, self-assembly monolayer membrane, or LB membrane, (3) using the conductive substrate as work electrode, and electrodepositing under const. elec. voltage or current to obtain ordered metal nanoparticles array, and (4) immersing the work electrode in solvent to remove polymer layer, repeating for 3-4 times, and drying with high pure nitrogen to obtain the title substrate. The method can be used in construction of most metal ordered structure, which has wide application in prepg. high sensitivity metal sensor and detector, prepg. Raman substrate, and in Raman detection.

IT ***3069-42-9*** , Octadecyltrimethoxysilane ***101947-16-4*** , (Heptadecafluoro-1,1,2,2-tetrahydrodecyl)triethoxysilane
RL: NUU (Other use, unclassified); USES (Uses)
(method for constructing surface enhanced substrate with metal ordered structure)
RN 3069-42-9 CAPLUS
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 8 in file .gra /

RN 101947-16-4 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 9 in file .gra /

L10 ANSWER 5 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
ACCESSION NUMBER: 2007:157795 CAPLUS <<LOGINID::20071129>>
DOCUMENT NUMBER: 146:488210
TITLE: Surface Design for Precise Control of Spatial Growth of a Mesostructured Inorganic/Organic Film on a Large-Scale Area
AUTHOR(S): Hozumi, Atsushi; Kojima, Satoshi; Nagano, Shusaku; Seki, Takahiro; Shirahata, Naoto; Kameyama, Tetsuya
CORPORATE SOURCE: National Institute of Advanced Industrial Science Technology (AIST), 2266-98 Anagahora, Shimo-shidami, Moriyama-ku, Nagoya, 463-8560, Japan
SOURCE: Langmuir (2007), 23(6), 3265-3272
CODEN: LANGD5; ISSN: 0743-7463
PUBLISHER: American Chemical Society
DOCUMENT TYPE: Journal
LANGUAGE: English

AB A microfabrication technique is presented to fabricate a mesostructured inorg./org. composite film, i.e., silica/cetyltrimethylammonium chloride (CTAC) film, with near-perfect site-selectivity on a large surface area based on a spatially regulated growth method. To precisely regulate the site-selective growth of this mesocomposite film at the solid/liq. interface, we designed a novel microtemplate consisting of a

"dual-component" self-assembled monolayer (SAM) with alternating hydrophobic trifluorocarbon (CF3) and cationic amino (NH2) groups. First, (heptadecafluoro-1,1,2,2-tetrahydrodecyl)trimethoxysilane (FAS)-SAM was formed onto Si substrate covered with native oxide (SiO2/Si) from ***vapor*** phase. The substrate was then photolithog. micropatterned using 172 nm vacuum UV light. Finally, the micropatterned FAS-SAM was immersed in a soln. of 1 vol % (aminoethylaminomethyl)phenethyltrimethoxysilane (AEAMPS) in abs. toluene. Due to these treatments, a dual-SAM microtemplate with CF3- and NH2-terminated surfaces was fabricated, as evidenced by lateral force microscopy, ellipsometry, and XPS. Using this template, the microfabrication of a mesocomposite film was demonstrated. As a control, the micropatterned hydrophobic FAS-SAM template (composed of CF3- and OH-terminated surfaces) was also treated under the same conditions. Optical microscopy and at. force microscopy confirmed that the formation of the continuous mesocomposite film proceeded only on the FAS-SAM-covered regions, while the AEAMPS-SAM-covered regions remained free of deposits. This shielding effect also remained const. regardless of the pattern's geometry, i.e., the interval distance between the FAS-SAM-covered areas in the pattern. Through this approach, we were able to obtain well-defined 5-, 10-, and 20-.mu.m wide mesocomposite microlines over the entire 10 .times. 10 mm2 area with high area-selectivity. On the other hand, when the SiO2 regions were not terminated with the cationic NH2 groups, cluster formation proceeded not only on the hydrophobic CF3 regions but also on the SiO2 regions, particularly with an increase in the pattern interval distance, resulting in lower final pattern resoln.

IT ***75822-22-9D*** , ***silicon*** bound ***83048-65-1D*** , (Heptadecafluoro-1,1,2,2-tetrahydrodecyl)trimethoxysilane, ***silicon*** bound
RL: NUU (Other use, unclassified); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)
(prepn. of mesostructured inorg-org. composite film)

RN 75822-22-9 CAPLUS
CN 1,2-Ethanediamine, N1-[[4-[2-(trimethoxysilyl)ethyl]phenyl]methyl]- (CA INDEX NAME)

/ Structure 10 in file .gra /

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 11 in file .gra /

REFERENCE COUNT: 81 THERE ARE 81 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

=> d hitstr 11-51

L10 ANSWER 11 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***101947-16-4*** , 1H,1H,2H,2H-Perfluorodecyl triethoxysilane
RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PRP (Properties); PYP (Physical process); PROC (Process); USES (Uses)
(surface modification of ***silicon*** and polydimethylsiloxane surfaces with ***vapor*** -phase-deposited ultrathin fluorosilane films for micro- and nanofluidic devices)
RN 101947-16-4 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 12 in file .gra /

L10 ANSWER 12 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***101947-16-4***
RL: PEP (Physical, engineering or chemical process); PYP (Physical process); PROC (Process)
(hydrophobic agents; rain-proof glass windows with a ***silicon*** -contg. hydrophobic surface of improved durability)
RN 101947-16-4 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 13 in file .gra /

L10 ANSWER 13 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***85712-15-8D*** , Methyloctyldimethoxysilane, ***silicon*** bound
***85857-17-6D*** , ***silicon*** bound
RL: CPS (Chemical process); PEP (Physical, engineering or chemical process); PRP (Properties); PROC (Process)
(prepn. of superhydrophobic SAM surface)
RN 85712-15-8 CAPLUS
CN Silane, dimethoxymethyloctyl- (CA INDEX NAME)

/ Structure 14 in file .gra /

RN 85857-17-6 CAPLUS
CN Silane, dimethoxymethyl(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)-(9CI) (CA INDEX NAME)

/ Structure 15 in file .gra /

L10 ANSWER 14 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***101947-16-4*** , 1H,1H,2H,2H-Perfluorodecyltriethoxysilane
RL: RCT (Reactant); RACT (Reactant or reagent)
(micropatterning of SrBi2Ta2O9 ferroelec. thin films using selective deposition)
RN 101947-16-4 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 16 in file .gra /

L10 ANSWER 15 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***101947-16-4*** , 1H,1H,2H,2H,-Perfluorodecyltriethoxysilane
RL: BUU (Biological use, unclassified); BIOL (Biological study); USES (Uses)
(nanoscale patterning of protein using electron beam lithog. of fluorinated organosilane self-assembled monolayers and high-affinity biotin-streptavidin binding system)
RN 101947-16-4 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 17 in file .gra /

L10 ANSWER 16 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***83048-65-1*** , (Heptadecafluoro-1,1,2,2-tetrahydrodecyl) trimethoxysilane
RL: CPS (Chemical process); PEP (Physical, engineering or chemical process); PROC (Process)
(self-assembled monolayer; effect of oxide nanoskin on SAM formation on polymeric surface)
RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 18 in file .gra /

L10 ANSWER 17 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***1067-25-0*** , Propyltrimethoxysilane ***101947-16-4*** , Heptadecafluoro-1,1,2,2-tetrahydrodecyltriethoxysilane
RL: MOA (Modifier or additive use); USES (Uses)
(liq. and ***vapor*** phase silanes coating for release of thin film microelectromech. systems)
RN 1067-25-0 CAPLUS
CN Silane, trimethoxypropyl- (CA INDEX NAME)

/ Structure 19 in file .gra /

RN 101947-16-4 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 20 in file .gra /

L10 ANSWER 18 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***3069-21-4*** ***3069-40-7*** ***3069-42-9*** , Octadecyltrimethoxysilane ***16415-12-6*** , HexadecyltrimethoxySilane ***83048-65-1*** , 2-(Perfluorooctyl)ethyltrimethoxysilane ***85857-16-5*** , 2-(Perfluorohexyl)ethyltrimethoxysilane
RL: PEP (Physical, engineering or chemical process); PRP (Properties); PYP (Physical process); PROC (Process)
(tribol. properties of organosilane monolayers prepd. by chem. ***vapor*** adsorption method on ***silicon*** substrates)
RN 3069-21-4 CAPLUS
CN Silane, dodecyltrimethoxy- (CA INDEX NAME)

/ Structure 21 in file .gra /

RN 3069-40-7 CAPLUS
CN Silane, trimethoxyoctyl- (CA INDEX NAME)

/ Structure 22 in file .gra /

RN 3069-42-9 CAPLUS
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 23 in file .gra /

RN 16415-12-6 CAPLUS
CN Silane, hexadecyltrimethoxy- (CA INDEX NAME)

/ Structure 24 in file .gra /

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 25 in file .gra /

RN 85857-16-5 CAPLUS
CN Silane, trimethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA INDEX NAME)

/ Structure 26 in file .gra /

L10 ANSWER 19 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***159412-13-2*** ***208645-23-2*** ***805246-08-6*** ***805246-19-9***
RL: TEM (Technical or engineered material use); USES (Uses)
(anti-stain film; anti-stain thin film formation onto glass, PET or cellulose triacetate film)
RN 159412-13-2 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy-, homopolymer (CA INDEX NAME)

CM 1

CRN 83048-65-1
CMF C13 H13 F17 O3 Si

/ Structure 27 in file .gra /

RN 208645-23-2 CAPLUS

CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)-, homopolymer (CA INDEX NAME)

CM 1

CRN 101947-16-4
CMF C16 H19 F17 O3 Si

/ Structure 28 in file .gra /

RN 805246-08-6 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)dimethoxymethyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 83038-84-0
CMF C13 H13 F17 O2 Si

/ Structure 29 in file .gra /

RN 805246-19-9 CAPLUS
CN Poly[oxy(1,1,2,2,3,3-hexafluoro-1,3-propanediyl)], .alpha.-(heptafluoropropyl)-.omega.-[1,1,2,2-tetrafluoro-4-(trimethoxysilyl)butoxy]-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 365545-93-3
CMF (C3 F6 O)n C10 H13 F11 O4 Si
CCI PMS

/ Structure 30 in file .gra /

L10 ANSWER 20 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***101947-16-4*** , Heptadecafluoro-1,1,2,2-tetrahydrodecyltriethoxysilane
RL: NUU (Other use, unclassified); USES (Uses)
(coupling agent; method of coating microelectromech. devices)
RN 101947-16-4 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 31 in file .gra /

L10 ANSWER 21 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***52686-75-6*** ***94237-08-8*** ***193674-11-2***
RL: BUU (Biological use, unclassified); DEV (Device component use); BIOL (Biological study); USES (Uses)
(development of substrate surface modification methods for biochem. immobilization in biochips)
RN 52686-75-6 CAPLUS
CN Silane, ethylmethoxydimethyl- (9CI) (CA INDEX NAME)

/ Structure 32 in file .gra /

RN 94237-08-8 CAPLUS
CN Silane, methoxydimethyl(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA INDEX NAME)

/ Structure 33 in file .gra /

RN 193674-11-2 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)methoxydimethyl- (CA INDEX NAME)

/ Structure 34 in file .gra /

L10 ANSWER 22 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***101947-16-4*** , AY 43-158E
RL: RCT (Reactant); RACT (Reactant or reagent)
(deposition from; method and app. for manufg. anti-reflective films)
RN 101947-16-4 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 35 in file .gra /

L10 ANSWER 23 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***919-30-2*** , 3-Aminopropyltriethoxysilane ***3069-42-9*** , Octadecyltrimethoxysilane ***83048-65-1*** , (Heptadecafluoro-1,1,2,2-tetrahydrodecyl)trimethoxysilane
RL: ARU (Analytical role, unclassified); DEV (Device component use); PEP (Physical, engineering or chemical process); PYP (Physical process); ANST (Analytical study); PROC (Process); USES (Uses)
(formation of mol. templates for fabricating on-chip biosensing devices)
RN 919-30-2 CAPLUS
CN 1-Propanamine, 3-(triethoxysilyl)- (CA INDEX NAME)

/ Structure 36 in file .gra /

RN 3069-42-9 CAPLUS
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 37 in file .gra /

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 38 in file .gra /

L10 ANSWER 24 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***3069-29-2*** , n-2-Aminoethyl-3-aminopropylmethyldimethoxysilane
***85857-16-5*** , 2-Perfluorohexyl ethyltrimethoxysilane
RL: CPS (Chemical process); PEP (Physical, engineering or chemical process); PRP (Properties); PYP (Physical process); PROC (Process)
(site-specific adsorption and arrangement of polystyrene microparticles on Si, patterned with organosilane monolayer through photolithog. process)
RN 3069-29-2 CAPLUS
CN 1,2-Ethanediamine, N1-[3-(dimethoxymethylsilyl)propyl]- (CA INDEX NAME)

/ Structure 39 in file .gra /

RN 85857-16-5 CAPLUS
CN Silane, trimethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA INDEX NAME)

/ Structure 40 in file .gra /

L10 ANSWER 25 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***2530-83-8*** , (3-Glycidoxypropyl)trimethoxysilane ***51851-37-7*** , 1H,1H,2H,2H-Perfluorooctyltriethoxysilane
RL: RCT (Reactant); RACT (Reactant or reagent)
( ***vapor*** pressures of precursors for CVD of Si-based films)
RN 2530-83-8 CAPLUS
CN Oxirane, 2-[[3-(trimethoxysilyl)propoxy]methyl]- (CA INDEX NAME)

/ Structure 41 in file .gra /

RN 51851-37-7 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA

INDEX NAME)

/ Structure 42 in file .gra /

L10 ANSWER 26 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***18536-91-9*** , Dodecyltriethoxysilane ***101947-16-4***
RL: TEM (Technical or engineered material use); USES (Uses)
(coating material; self-assembled monolayer coatings on nanostencils for redn. of contaminant adhesion)
RN 18536-91-9 CAPLUS
CN Silane, dodecyltriethoxy- (CA INDEX NAME)

/ Structure 43 in file .gra /

RN 101947-16-4 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 44 in file .gra /

L10 ANSWER 27 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***193756-76-2***
RL: MOA (Modifier or additive use); USES (Uses)
(hydrophobic treatment agent; prepn. of hard, transparent and ultra water-repellent silica films by microwave plasma-enhanced CVD at low substrate temps. from trimethylmethoxysilane-CO2 gas mixts.)
RN 193756-76-2 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy-, polymer with tetramethylsilane (9CI) (CA INDEX NAME)

CM 1

CRN 83048-65-1
CMF C13 H13 F17 O3 Si

/ Structure 45 in file .gra /

CM 2

CRN 75-76-3
CMF C4 H12 Si

/ Structure 46 in file .gra /

L10 ANSWER 28 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***101947-16-4*** , (Heptadecafluoro-1,1,2,2-tetrahydro)decyl-triethoxysilane
RL: CPS (Chemical process); PEP (Physical, engineering or chemical process); PROC (Process)
(method for making thin film and electronic app.)
RN 101947-16-4 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 47 in file .gra /

L10 ANSWER 29 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***51851-37-7*** , (Tridecafluoro-1, 1, 2, 2-tetrahydro) octyl triethoxysilane
RL: CPS (Chemical process); PEP (Physical, engineering or chemical process); PROC (Process)
(formation method of ***silicon*** thin film)
RN 51851-37-7 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA INDEX NAME)

/ Structure 48 in file .gra /

L10 ANSWER 30 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***3069-42-9*** , n-Octadecyltrimethoxysilane ***51895-58-0***
***83048-65-1***
RL: PEP (Physical, engineering or chemical process); PRP (Properties); PYP (Physical process); PROC (Process)
(surface potential images of self-assembled monolayers patterned by organosilanes)
RN 3069-42-9 CAPLUS
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 49 in file .gra /

RN 51895-58-0 CAPLUS
CN 1,6-Hexanediamine, N1-[3-(trimethoxysilyl)propyl]- (CA INDEX NAME)

/ Structure 50 in file .gra /

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 51 in file .gra /

L10 ANSWER 31 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***3069-42-9*** , Octadecyltrimethoxysilane ***51895-58-0***
***83048-65-1***
RL: CPS (Chemical process); PEP (Physical, engineering or chemical process); PROC (Process)
(organosilane self-assembled monolayers formed at the ***vapor***/solid interface)
RN 3069-42-9 CAPLUS
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 52 in file .gra /

RN 51895-58-0 CAPLUS
CN 1,6-Hexanediamine, N1-[3-(trimethoxysilyl)propyl]- (CA INDEX NAME)

/ Structure 53 in file .gra /

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 54 in file .gra /

L10 ANSWER 32 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***3069-42-9*** , Octadecyltrimethoxysilane ***83048-65-1***
RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
(organosilane self-assembled monolayer photoresists for vacuum-UV lithog.)
RN 3069-42-9 CAPLUS
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 55 in file .gra /

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 56 in file .gra /

L10 ANSWER 33 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***83048-65-1*** ***85857-16-5***
RL: PRP (Properties)
(lateral force and water contact angle on fluoroalkylsilane self-assembled monolayers dependent on mol. ordering)
RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 57 in file .gra /

RN 85857-16-5 CAPLUS
CN Silane, trimethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA INDEX NAME)

/ Structure 58 in file .gra /

L10 ANSWER 34 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***429-60-7*** , 3,3,3-Trifluoropropyltrimethoxysilane
RL: PEP (Physical, engineering or chemical process); PRP (Properties); PYP (Physical process); PROC (Process)
(activated; surface potential contrasts between Si surfaces covered and uncovered with organosilane self-assembled monolayer)
RN 429-60-7 CAPLUS
CN Silane, trimethoxy(3,3,3-trifluoropropyl)- (CA INDEX NAME)

/ Structure 59 in file .gra /

IT ***3069-42-9*** , n-Octadecyltrimethoxysilane ***13822-56-5*** , Aminopropyltrimethoxysilane ***83048-65-1***
RL: PEP (Physical, engineering or chemical process); PRP (Properties); PYP (Physical process); PROC (Process)
(surface potential contrasts between Si surfaces covered and uncovered with organosilane self-assembled monolayer)
RN 3069-42-9 CAPLUS
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 60 in file .gra /

RN 13822-56-5 CAPLUS
CN 1-Propanamine, 3-(trimethoxysilyl)- (CA INDEX NAME)

/ Structure 61 in file .gra /

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 62 in file .gra /

L10 ANSWER 35 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***83048-65-1***
RL: PEP (Physical, engineering or chemical process); PROC (Process)
(deposition of; in surface patterning by gathering hydrophilic fluid on latent pattern comprising hydrophilic region and water-repellent region)
RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 63 in file .gra /

L10 ANSWER 36 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***3069-42-9*** , Octadecyltrimethoxysilane ***83048-65-1*** , (Heptadecafluoro-1,1,2,2-tetrahydrodecyl) trimethoxysilane

RL: PEP (Physical, engineering or chemical process); PRP (Properties); PROC (Process)
(zeta potentials of planar ***silicon*** plates covered with alkyl- and fluoroalkylsilane self-assembled monolayers)
RN 3069-42-9 CAPLUS
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 64 in file .gra /

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 65 in file .gra /

L10 ANSWER 37 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***83048-65-1*** , KBM 7803
RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)
(targets impregnated with; sintered metal targets impregnated with perfluoropolyether group-contg. alkoxysilanes for formation of antistaining and water-repellent coatings on antireflective materials)
RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 66 in file .gra /

L10 ANSWER 38 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***3069-42-9*** , Octadecyltrimethoxysilane ***83048-65-1***
RL: PEP (Physical, engineering or chemical process); PROC (Process)
(micropatterning of ***silicon*** substrates using alkyl- and fluoroalkylsilane self-assembled monolayers and vacuum-UV)
RN 3069-42-9 CAPLUS
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 67 in file .gra /

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 68 in file .gra /

L10 ANSWER 39 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***3069-42-9*** , Octadecyl-trimethoxysilane ***83048-65-1***
RL: PEP (Physical, engineering or chemical process); PROC (Process)
(hydrophobic layer precursor; effects of surface functional groups and microstructures on morphol. of mesoporous silica grown on org. surfaces)
RN 3069-42-9 CAPLUS
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 69 in file .gra /

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 70 in file .gra /

L10 ANSWER 40 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***190579-86-3*** , Triethoxy(3,3,4,4,5,5,6,6,7,7,7-undecafluoroheptyl)silane
RL: TEM (Technical or engineered material use); USES (Uses)
(manuf. of water-repellent coatings on optical substrates by

electron-beam ***vapor*** deposition of org. ***silicon*** compds. impregnated in porous carriers)

RN 190579-86-3 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,7-undecafluoroheptyl)- (CA INDEX NAME)

/ Structure 71 in file .gra /

L10 ANSWER 41 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***83048-65-1*** , KBM7803
RL: NUU (Other use, unclassified); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)
(in manuf. of water-repellent ***silicon*** oxide film)

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 72 in file .gra /

L10 ANSWER 42 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***83048-65-1***
RL: NUU (Other use, unclassified); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)
(precursor; microwave plasma CVD for transparent and hard Si oxide films with graded compn.)

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 73 in file .gra /

L10 ANSWER 43 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***83048-65-1***
RL: DEV (Device component use); PEP (Physical, engineering or chemical process); PRP (Properties); PROC (Process); USES (Uses)
(final precursor gas contg.; prepn. of ***silicon*** oxide films having a water-repellent surface by multiple-step microwave plasma-enhanced chem. ***vapor*** deposition)

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 74 in file .gra /

L10 ANSWER 44 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***83048-65-1***
RL: MOA (Modifier or additive use); PEP (Physical, engineering or chemical process); PROC (Process); USES (Uses)
(effects of Me and perfluoroalkyl groups on water repellency of ***silicon*** oxide films prepd. by microwave plasma-enhanced CVD)

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 75 in file .gra /

L10 ANSWER 45 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***101947-16-4*** , 1H,1H,2H,2H,-Perfluorodecyltriethoxysilane
RL: PEP (Physical, engineering or chemical process); PRP (Properties); PROC (Process)
( ***vapor*** phase silylation of, on germanium/germanium oxide surfaces, mol. orientation in thin films and surface coverage of)

RN 101947-16-4 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 76 in file .gra /

L10 ANSWER 46 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***429-60-7*** ***83048-65-1*** ***85857-16-5***
RL: PEP (Physical, engineering or chemical process); PROC (Process)
(precursor; coating of transparent water-repellent thin films by plasma-enhanced CVD)
RN 429-60-7 CAPLUS
CN Silane, trimethoxy(3,3,3-trifluoropropyl)- (CA INDEX NAME)

/ Structure 77 in file .gra /

RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 78 in file .gra /

RN 85857-16-5 CAPLUS
CN Silane, trimethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA INDEX NAME)

/ Structure 79 in file .gra /

L10 ANSWER 47 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***159412-13-2P***
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(manuf. of water-repellent coatings on resin substrates by high frequency plasma ***vapor*** deposition of perfluoroalkylsilanes)
RN 159412-13-2 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy-, homopolymer (CA INDEX NAME)

CM 1

CRN 83048-65-1
CMF C13 H13 F17 O3 Si

/ Structure 80 in file .gra /

IT ***83048-65-1*** , KBM 7803
RL: PEP (Physical, engineering or chemical process); PROC (Process)
(manuf. of water-repellent coatings on resin substrates by high frequency plasma ***vapor*** deposition of perfluoroalkylsilanes)
RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 81 in file .gra /

L10 ANSWER 48 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***159412-13-2*** , (Heptadecafluoro-1,1,2,2-tetrahydrodecyl)-1-trimethoxysilane homopolymer
RL: PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(plasma-enhanced chem. ***vapor*** deposition of water-repellent and transparent fluorine-contg. films on polycarbonate and ***silicon*** and glass)
RN 159412-13-2 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy-, homopolymer (CA INDEX NAME)

CM 1

CRN 83048-65-1
CMF C13 H13 F17 O3 Si

/ Structure 82 in file .gra /

L10 ANSWER 49 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***83048-65-1***
RL: PEP (Physical, engineering or chemical process); PRP (Properties); PROC (Process)
(effects of substrate temp. on properties of fluorine contained ***silicon*** oxide films prepd. by microwave plasma-enhanced CVD)
RN 83048-65-1 CAPLUS
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 83 in file .gra /

L10 ANSWER 50 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***160687-77-4P*** ***160718-35-4P***
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(water-repellent fluorine-contg. ***silicon*** oxide coatings on glass and ***silicon*** wafer)
RN 160687-77-4 CAPLUS
CN Silicic acid (H4SiO4), tetramethyl ester, polymer with triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)silane (9CI) (CA INDEX NAME)

CM 1

CRN 101947-16-4
CMF C16 H19 F17 O3 Si

/ Structure 84 in file .gra /

CM 2

CRN 681-84-5
CMF C4 H12 O4 Si

/ Structure 85 in file .gra /

RN 160718-35-4 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)-, polymer with silane (9CI) (CA INDEX NAME)

CM 1

CRN 101947-16-4
CMF C16 H19 F17 O3 Si

/ Structure 86 in file .gra /

CM 2

CRN 7803-62-5
CMF H4 Si

/ Structure 87 in file .gra /

L10 ANSWER 51 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
IT ***101947-16-4***
RL: RCT (Reactant); RACT (Reactant or reagent)
(reaction of, with ***silicon*** surface, in prepn. of polyimide thin film)
RN 101947-16-4 CAPLUS
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 88 in file .gra /

=> d bib 13, 17, 18, 21, 46

L10 ANSWER 13 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
AN 2005:106536 CAPLUS <<LOGINID::20071129>>
DN 142:361489
TI Fabrication of Superhydrophobic Surfaces by Self-Assembly and Their Water-Adhesion Properties
AU Song, Xiaoyan; Zhai, Jin; Wang, Yilin; Jiang, Lei
CS Center for Molecular Sciences, Institute of Chemistry, Chinese Academy of Sciences, Beijing, 100080, Peop. Rep. China
SO Journal of Physical Chemistry B (2005), 109(9), 4048-4052
CODEN: JPCBFK; ISSN: 1520-6106
PB American Chemical Society
DT Journal
LA English
RE.CNT 31 THERE ARE 31 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L10 ANSWER 17 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
AN 2006:143210 CAPLUS <<LOGINID::20071129>>
DN 144:499593
TI Liquid and ***vapor*** phase silanes coating for the release of thin film MEMS
AU Parvais, B.; Pallandre, A.; Jonas, A. M.; Raskin, J.-P.
CS Research Center in Micro and Nanoscopic Materials and Electronic Devices (CERMIN), Universite catholique de Louvain, Louvain-la-Neuve, B-1348, Belg.
SO IEEE Trans. Device Mater. Reliab. (2005), 5(2), 250-254
CODEN: ITDMA2; ISSN: 1530-4388
URL: http://ieeexplore.ieee.org/iel5/7298/31396/01458741.pdf?isnumber=31396&prod=JNL&arnumber=1458741&arSt=+250&ared=+254&arAuthor=Parvais%2C+B.%3B+Pallandre%2C+A.%3B+Jonas%2C+A.M.%3B+Raskin%2C+J.-P.
PB Institute of Electrical and Electronics Engineers
DT Journal; (online computer file)
LA English
RE.CNT 18 THERE ARE 18 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L10 ANSWER 18 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
AN 2005:422268 CAPLUS <<LOGINID::20071129>>
DN 144:281105
TI Macro- and nanotribological properties of organosilane monolayers prepared by a chemical ***vapor*** adsorption method on ***silicon*** substrates
AU Ishida, H.; Koga, T.; Morita, M.; Otsuka, H.; Takahara, A.
CS Graduate School of Engineering, Kyushu University, Fukuoka, 812-8581, Japan
SO Tribology Letters (2005), 19(1), 3-8
CODEN: TRLEFS; ISSN: 1023-8883
PB Springer
DT Journal
LA English
RE.CNT 21 THERE ARE 21 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L10 ANSWER 21 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
AN 2004:674693 CAPLUS <<LOGINID::20071129>>
DN 141:168967
TI Development of substrate surface modification methods for biochemical immobilization in biochips
IN Kim, Hun-Ki; Lee, Jung-Suk; Lim, Geun-Bae; Lee, Young-Sun
PA Samsung Electronics Co., Ltd., S. Korea
SO Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

| | PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|---|---|---|---|---|---|
| PI | JP 2004229663 | A | 20040819 | JP 2004-18353 | 20040127 |
| | KR 2004069063 | A | 20040804 | KR 2003-5486 | 20030128 |
| | EP 1452232 | A2 | 20040901 | EP 2004-1606 | 20040126 |
| | EP 1452232 | A3 | 20050720 | | |

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK

| | | | | | |
|---|---|---|---|---|---|
| | US 2004185480 | A1 | 20040923 | US 2004-765366 | 20040127 |
| | CN 1519562 | A | 20040811 | CN 2004-10005810 | 20040128 |
| PRAI | KR 2003-5486 | A | 20030128 | | |

L10 ANSWER 46 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN
AN 1997:622716 CAPLUS <<LOGINID::20071129>>
DN 127:310357
TI Coating of transparent water-repellent thin films by plasma-enhanced CVD
AU Takai, Osamu; Hozumi, Atsushi; Sugimoto, Nobuhisa
CS Department of Materials Processing Engineering, Nagoya University, Chikusa-ku, Nagoya, 464-01, Japan
SO Journal of Non-Crystalline Solids (1997), 218, 280-285
CODEN: JNCSBJ; ISSN: 0022-3093
PB Elsevier
DT Journal
LA English
RE.CNT 12 THERE ARE 12 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

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                  fields
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                  patents
 NEWS  8  MAY 22  CA/CAplus enhanced with IPC reclassification in Japanese
                  patents
 NEWS  9  JUN 27  CA/CAplus enhanced with pre-1967 CAS Registry Numbers
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 NEWS 13  JUL 02  LMEDLINE coverage updated
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 NEWS 15  JUL 02  CHEMCATS accession numbers revised
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 NEWS 17  JUL 16  CAplus enhanced with French and German abstracts
 NEWS 18  JUL 18  CA/CAplus patent coverage enhanced
 NEWS 19  JUL 26  USPATFULL/USPAT2 enhanced with IPC reclassification
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 NEWS 24  AUG 13  CA/CAplus enhanced with additional kind codes for granted
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 NEWS 25  AUG 20  CA/CAplus enhanced with CAS indexing in pre-1907 records
 NEWS 26  AUG 27  Full-text patent databases enhanced with predefined
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 NEWS 27  AUG 27  USPATOLD now available on STN
 NEWS 28  AUG 28  CAS REGISTRY enhanced with additional experimental
                  spectral property data

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               CURRENT MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP),
               AND CURRENT DISCOVER FILE IS DATED 05 JULY 2007.

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